

**METHOD FOR CONTROLLING CRITICAL DIMENSION BY UTILIZING
RESIST SIDEWALL PROTECTION**

Appl. No. : 10/707,259 Confirmation No. 1258
Applicant : Hsiu-Chun Lee,
Tse-Yao Huang,
Yi-Nan Chen
Filed : December 2, 2003
TC/A.U. : 1756
Examiner : CHACKO DAVIS, DABORAH
Docket No. : NTCP0028USA0
Customer No. : 27765

Commissioner for Patents
P.O. Box 1450
Alexandria VA 22313-1450

AMENDMENT

5 Sir:

In response to the Office action of September 22, 2006, please amend the above-identified application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

10 **Remarks/Arguments** begin on page 4 of this paper.